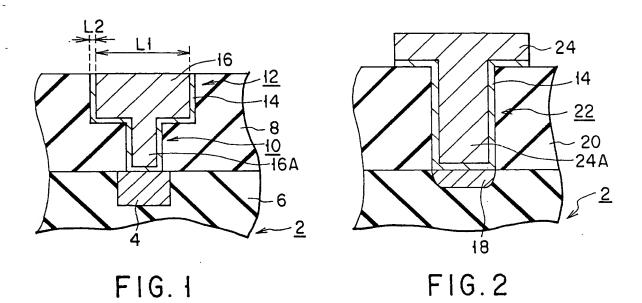
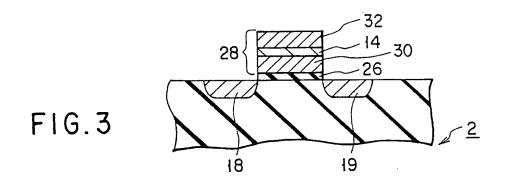
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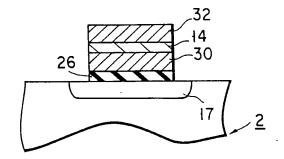
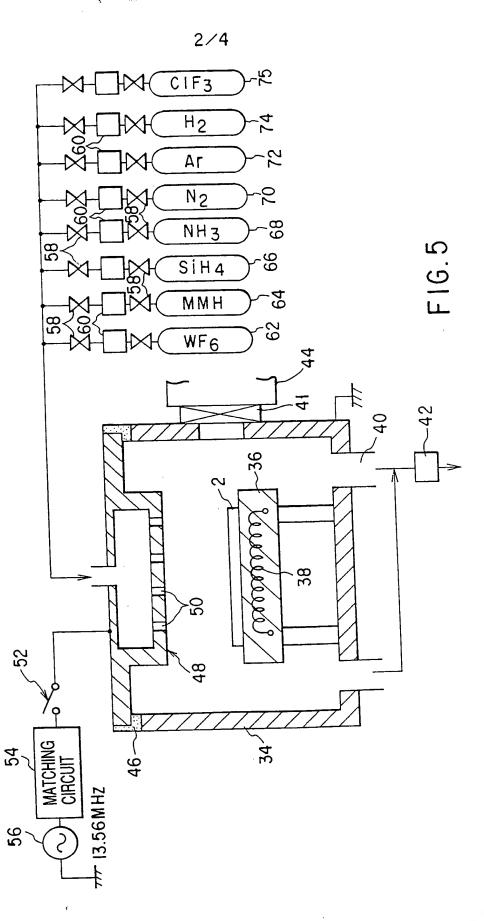
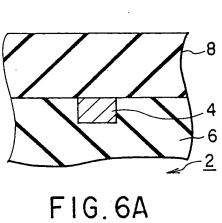


FIG.4



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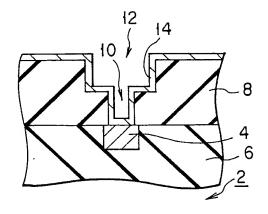
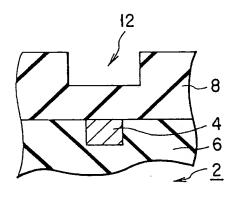


FIG.6D



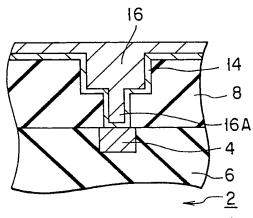
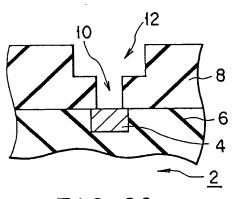


FIG. 6B

FIG. 6E



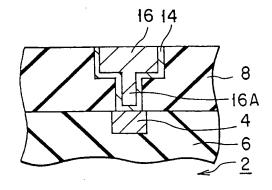


FIG.6C

FIG.6F



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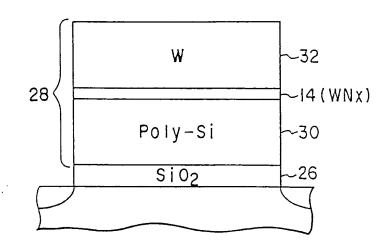


FIG.7

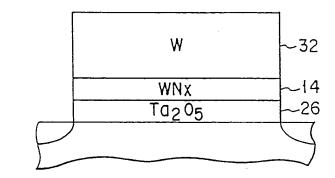


FIG.8

	COMPARATIVE EXAMPLE 1	COMPARATIVE EXAMPLE 2	PRESENT INVENTION
STRUCTURE	Poly / WSi	Poly / TiSi	Poly / WN / W
RESISTANCE VALUE (uohmcm)	50 -60	20 -30	10
HEAT RESISTANCE	1000	800	900
CHEMICAL RESISTANCE (HF)	GOOD	POOR	GOOD
ETCHING AMOUNT DURING FILM FORMATION	LARGE	SMALL	SMALL

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